

Efficiency Optimization of Ge-V Quantum Emitters in Single-Crystal Diamond upon Ion Implantation and HPHT Annealing

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The authors report on the characterization at the single-defect level of germanium-vacancy (GeV) centers in diamond produced upon Ge⁻ ion implantation and different subsequent annealing processes, with a specific focus on the effect of high-pressure-high-temperature (HPHT) processing on their quantum-optical properties. Different post-implantation annealing conditions are explored for the optimal activation of GeV centers, namely, 900 °C 2 h, 1000 °C 10 h, 1500 °C 1 h under high vacuum, and 2000 °C 15 min at 6 GPa pressure. A systematic analysis of the relevant emission properties, including the emission intensity in saturation regime and the excited state radiative lifetime, is performed on the basis of a set of ion-implanted samples, with the scope of identifying the most suitable conditions for the creation of GeV centers with optimal quantum-optical emission properties. The main performance parameter adopted here to describe the excitation efficiency of GeV centers as single-photon emitters is the ratio between the saturation optical excitation power and the emission intensity at saturation. The results show an up to eightfold emission efficiency increase in HPHT-treated samples with respect to conventional annealing in vacuum conditions, suggesting a suitable thermodynamic pathway toward the repeatable fabrication of ultra-bright GeV centers for single-photon generation purposes.

1. Introduction

Color centers in diamond represent an emerging class of solid-state systems for single-photon emission,^[1–8] with appealing applications in quantum-enhanced technologies, including quantum information processing and quantum sensing.^[9–18] Among them, point-defects related to group-IV impurities have displayed promising properties in terms of high photon emission rate, relatively narrow spectral signatures, and spin-dependent emission properties.^[19–26]

The identification of reliable pathways toward their reproducible fabrication is therefore crucial for a widespread adoption of these systems. The most convenient method to date is represented by the fabrication by ion implantation and subsequent high-temperature annealing, which enables in perspective the control on both the position and the number of individual emitters on a diamond chip.^[19,27–29] It is therefore


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